EEMF 6348 (MECH 6341 and MSEN 6348) Lithography and Nanofabrication (3 semester credit hours) Study of the principles, practical considerations, and instrumentation of major lithography technologies for nanofabrication of devices and materials. Advanced photolithography, electron beam lithography, nanoimprint lithography, x-ray lithography, ion beam lithography, soft lithography, and scanning probe lithography, basic resist and polymer science, applications in nanoelectronic and biomaterials. (3-0) Y